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BY
PATENT
10/30/01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Present Application:Applicants : Vishnu K. Agarwal and
Scott G. Meikle

Attorney Docket No. : 500453.04

Filed : Concurrently herewith

Title : POLISHING PADS AND PLANARIZING MACHINES FOR MECHANICAL
OR CHEMICAL-MECHANICAL PLANARIZATION OF
MICROELECTRONIC-DEVICE SUBSTRATE ASSEMBLIES, AND
METHODS FOR MAKING AND USING SUCH PADS AND MACHINES**Prior Application:**

Examiner : William P. Fletcher III

Art Unit : 1762

Serial No. : 09/621,021

PRELIMINARY AMENDMENTBox Patent Application
Commissioner of Patents
Washington, D.C. 20231

Sir:

Please amend the above-identified application as follows:

In the Specification:

Amend the specification by inserting a new section before the "Technical Field"

as follows:

-- CROSS-REFERENCE TO RELATED APPLICATIONSThis application is a continuation of pending United States Patent Application
No. 09/621,021, filed July 21, 2000, which is a divisional of United States Patent Application
No. 09/201,576, filed November 30, 1998. --
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In the Claims: ✓

Please cancel claims 1-54, 58, 60-64, 65-68, 71, and 73-79.

Respectfully submitted,

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